

CCD42-40 Ceramic AIMO Back Illuminated Compact Package High Performance CCD Sensor

e2v technologies

FEATURES

- 2048 by 2048 pixel format
- 13.5 μm square pixels
- Image area 27.6 x 27.6 mm
- Back Illuminated format for high quantum efficiency
- Full-frame operation
- Symmetrical anti-static gate protection
- Very low noise output amplifiers
- Dual responsivity output amplifiers
- Gated dump drain on output register
- 100% active area
- New compact footprint package
- Advanced inverted mode operation (AIMO)

APPLICATIONS

- Scientific Imaging
- Microscopy
- Medical Imaging



This version of the CCD42 family of CCD sensors has full-frame architecture. Back illumination technology, in combination with extremely low noise amplifiers, makes the device well suited to the most demanding applications requiring a high dynamic range. To improve the sensitivity further, the CCD is manufactured without anti-blooming structures.

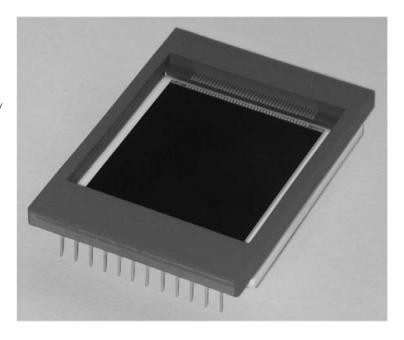
There are two low noise amplifiers in the readout register, one at each end. Charge can be made to transfer through either or both amplifiers by making the appropriate $R\emptyset$ connections. The readout register has a gate controlled dump drain to allow fast dumping of unwanted data.

The register is designed to accommodate four image pixels of charge and a summing well is provided capable of holding six image pixels of charge. The output amplifier has a feature to enable the responsivity to be reduced, allowing the reading of such large charge packets.

The advanced inverted mode operation (AIMO) gives a 100-times reduction in dark current with minimal full-well reduction and is suitable for use at Peltier temperatures.

Other variants of the CCD42-40 available are front illuminated format and non-inverted mode. In common with all e2v technologies CCD Sensors, the front illuminated CCD42-40 can be supplied with a fibre-optic window or taper, or with a phosphor coating.

Designers are advised to consult e2v technologies should they be considering using CCD sensors in abnormal environments or if they require customised packaging.



TYPICAL PERFORMANCE

(Low noise mode)

Maximum readout frequency					3	MHz
Output amplifier responsivity					4.5	5 μV/e ⁻
Peak signal				10	00	ke ⁻ /pixel
Dynamic range (at 20 kHz) .			33	333	:1	
Spectral range		2	00 -	- 106	60	nm
Readout noise (at 20 kHz) .					3	e rms

GENERAL DATA

Format

Image area									27.6 x 27.6	mm
Active pixels	(H)								. 2048	
	(∨)								2048 + 4	
Pixel size .									13.5 x 13.5	μm
Number of o	utput	am	plif	iers	;				2	
number of ur	ndersc	an	(se	rial) pi	ixel	S		50	
Fill factor .									. 100	%

Package

Package size	37.0 x 51.7 m	ım
Number of pins	24	
Inter-pin spacing	2.54 m	ım
Inter-row spacing across sensor	45.72 m	ım
Window material	. removable gla	ass
Package type	ceramic DIL arr	ау

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PERFORMANCE

	Min	Typical	Max	
Peak charge storage (see note 1)	80k	100k	-	e ⁻ /pixel
Peak output voltage (unbinned)	-	450	-	mV
Dark signal at 293 K (see notes 2 and 3)	-	250	500	e ⁻ /pixel/s
Dynamic range (see note 4)	-	33 333:1	-	
Charge transfer efficiency (see note 5): parallel serial	99.999 99.999	99.9999 99.9993	-	% %
Output amplifier responsivity: low noise mode (see note 3) high signal mode	3.0	4.5 1.5	6.0	μV/e ⁻ μV/e ⁻
Readout noise at 253 K: low noise mode (see notes 3 and 6) high signal mode		3.0 6.0	4.5 -	rms e ⁻ /pixel rms e ⁻ /pixel
Maximum readout frequency (see note 7)	-	20	3000	kHz
Dark signal non-uniformity at 293 K (std. deviation) (see notes 3 and 8)	-	60	125	e ⁻ /pixel/s
Output node capacity (see note 9)	-	1,000,000	-	e ⁻

Spectral Response at 253 K

	Mir	nimum Response (QE)	Maximum		
Wavelength (nm)	Basic Process Mid-band Coated	Basic Process Broadband Coated	Basic Process Uncoated	Response Non-uniformity (1ਰ)	
350	15	25	10	5	%
400	40	55	25	3	%
500	85	75	55	3	%
650	85	75	50	3	%
900	30	30	30	5	%

The uncoated process is suitable for soft X-ray and EUV applications.

ELECTRICAL INTERFACE CHARACTERISTICS

Electrode capacitances (measured at mid-clock level)

	Min	Typical	Max	
IØ/IØ interphase	-	18	-	nF
IØ/SS	-	33	-	nF
RØ/RØ interphase	-	80	-	pF
$R\varnothing/(SS + DG + OD)$	-	150	-	pF
Output impedance at typical operating conditions	-	350	-	Ω

NOTES

- 1. Signal level at which resolution begins to degrade.
- Measured between 253 and 293 K typically. The typical average (background) dark signal at any temperature T (kelvin) between 230 K and 300 K may be estimated from:

$$Q_d/Q_{d0} = 1.14x10^6T^3e^{-9080/T}$$

where Q_{d0} is the dark signal at 293 K.

- 3. Test carried out at e2v technologies on all sensors.
- 4. Dynamic range is the ratio of full-well capacity to readout noise measured at 253 K and 20 kHz readout frequency.
- 5. CCD characterisation measurements made using charge generated by X-ray photons of known energy.
- 6. Measured using a dual-slope integrator technique (i.e. correlated double sampling) with a 20 μs integration period.
- 7. Readout above 3 MHz can be achieved but performance to the parameters given cannot be guaranteed.
- 8. Measured between 253 and 293 K, excluding white defects.
- 9. With output circuit configured in low responsivity/high capacity mode (OG2 high).

BLEMISH SPECIFICATION

Traps Pixels where charge is temporarily held.

Traps are counted if they have a capacity greater than 200 e^- at 253 K.

greater than 200 c at 200 K.

Slipped columns Are counted if they have an amplitude

greater than 200 e^- .

Black spots Are counted when they have a signal level of less than 80% of the local mean at a

signal level of approximately half full-well.

White spots Are counted when they have a generation rate 125 times the specified maximum dark

signal generation rate (measured between 253 and 293 K). The typical temperature dependence of white spot blemishes is

given by:

 $Q_d/Q_{d0} = 122T^3e^{-6400/T}$

Column defects A column which contains at least 50 white or 50 black defects.

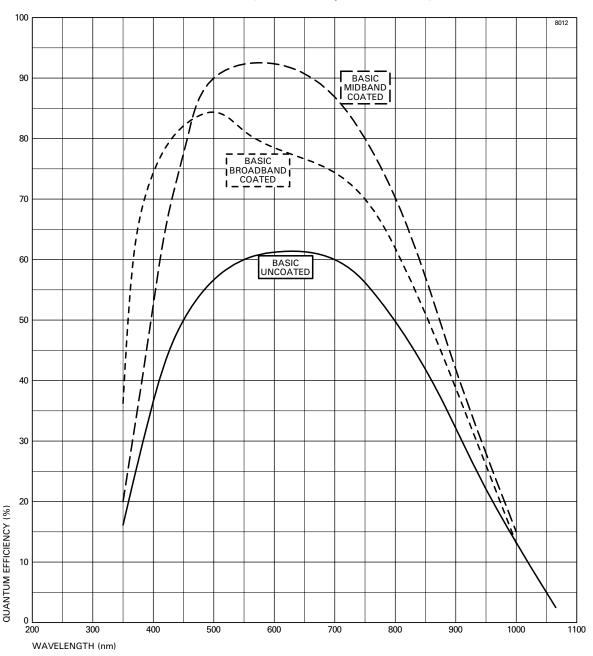
GRADE	0	1	2
Column defects; black or white	0	3	6
Black spots	100	150	250
Traps > 200 e-	10	20	30
White spots	100	150	200

Grade 5

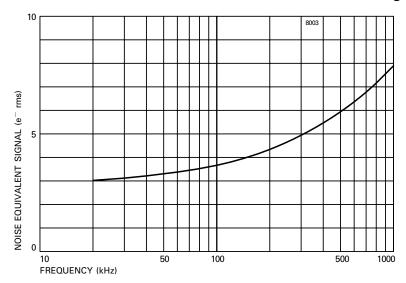
Devices which are fully functional, with image quality below that of grade 2, and which may not meet all other performance parameters.

Note The effect of temperature on defects is that traps will be observed less at higher temperatures but more may appear below 253 K. The amplitude of white spots and columns will decrease rapidly with temperature.

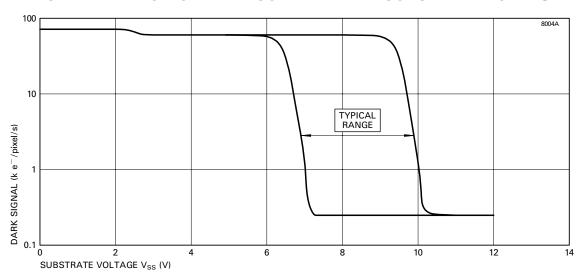
TYPICAL SPECTRAL RESPONSE (At -20 °C, no window)



TYPICAL OUTPUT CIRCUIT NOISE (Measured using clamp and sample)

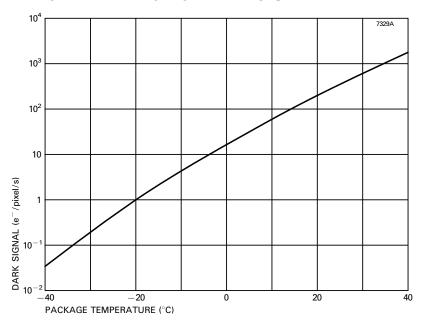


TYPICAL VARIATION OF DARK CURRENT WITH SUBSTRATE VOLTAGE AT 20 $^{\circ}\text{C}$

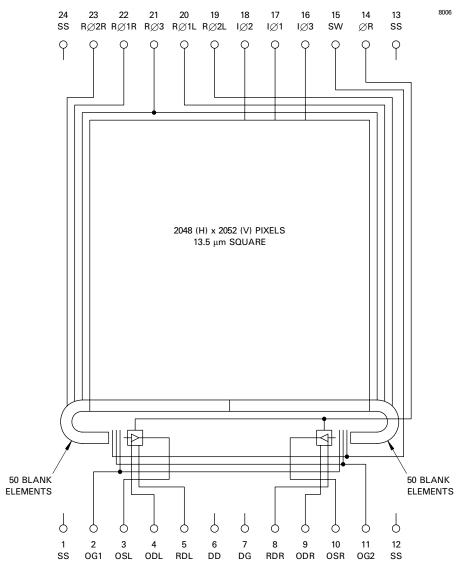


100012, page 4 © e2v technologies

TYPICAL VARIATION OF DARK SIGNAL WITH TEMPERATURE



DEVICE SCHEMATIC



CONNECTIONS, TYPICAL VOLTAGES AND ABSOLUTE MAXIMUM RATINGS

			CLOCK LOW	CLOCK HIGH OR DC LEVEL (V)			MAXIMUM RATINGS
PIN	REF	DESCRIPTION	Typical	Min	Typical	Max	with respect to V_{SS}
1	SS	Substrate	n/a	8	9.5	11	-
2	OG1	Output gate 1	n/a	2	3	4	<u>+</u> 20 V
3	OSL	Output transistor source (left)	n/a		see note 9		-0.3 to +25 V
4	ODL	Output drain (left)	n/a	27	29	31	-0.3 to +25 V
5	RDL	Reset drain (left)	n/a	15	17	19	-0.3 to +25 V
6	DD	Dump drain	n/a	22	24	26	-0.3 to +25 V
7	DG	Dump gate (see note 10)	0	-	12	15	<u>+</u> 20 V
8	RDR	Reset drain (right)	n/a	15	17	19	-0.3 to +25 V
9	ODR	Output drain (right)	n/a	27	29	31	-0.3 to +25 V
10	OSR	Output transistor source (right)	n/a		see note 9		-0.3 to +25 V
11	OG2	Output gate 2 (see note 11)	4	16	20	24	<u>+</u> 20 V
12	SS	Substrate	n/a	8	9.5	11	-
13	SS	Substrate	n/a	8	9.5	11	-
14	ØR	Reset gate	0	8	12	15	<u>+</u> 20 V
15	SW	Summing well		(Clock as RØ	13	<u>+</u> 20 V
16	IØ3	Image area clock, phase 3	0	8	15	16	<u>+</u> 20 V
17	IØ1	Image area clock, phase 1	0	8	15	16	<u>+</u> 20 V
18	IØ2	Image area clock, phase 2	0	8	15	16	<u>+</u> 20 V
19	RØ2L	Register clock phase 2 (left)	1	8	11	15	<u>+</u> 20 V
20	RØ1L	Register clock phase 1 (left)	1	8	11	15	<u>+</u> 20 V
21	RØ3	Register clock phase 3	1	8	11	15	<u>+</u> 20 V
22	RØ1R	Register clock phase 1 (right)	1	8	11	15	<u>+</u> 20 V
23	RØ2R	Register clock phase 2 (right)	1	8	11	15	<u>+</u> 20 V
24	SS	Substrate	n/a	8	9.5	11	-

If all voltages are set to the typical values, operation at or close to specification should be obtained. Some adjustment within the range specified may be required to optimise performance. Refer to the specific device test data if possible.

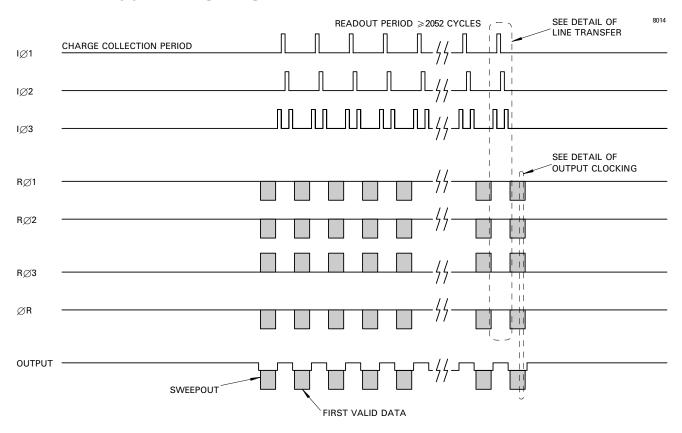
Maximum voltages between pairs of pins:

NOTES

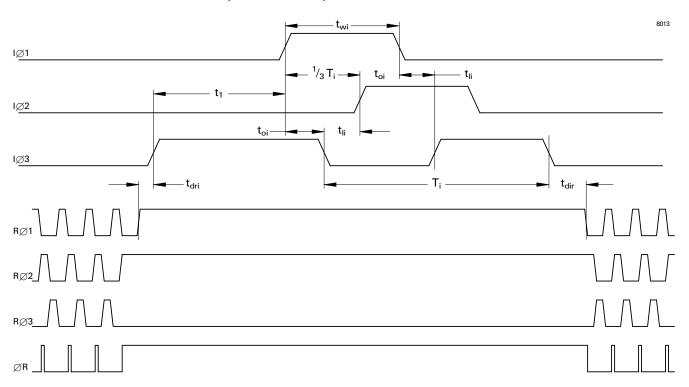
- 9. Not critical; OS = 3 to 5 V below OD typically. Connect to ground using a 3 to 5 mA current source or appropriate load resistor (typically 5 to 10 k Ω).
- 10. This gate is normally low. It should be pulsed high for charge dump.
- 11. OG2 = OG1 + 1 V for operation of the output in high responsivity, low noise mode. For operation at low responsivity, high signal, OG2 should be set high.
- 12. With the R \varnothing connections shown, the device will operate through both outputs simultaneously. In order to operate from the left output only, R \varnothing 1(R) and R \varnothing 2(R) should be reversed.

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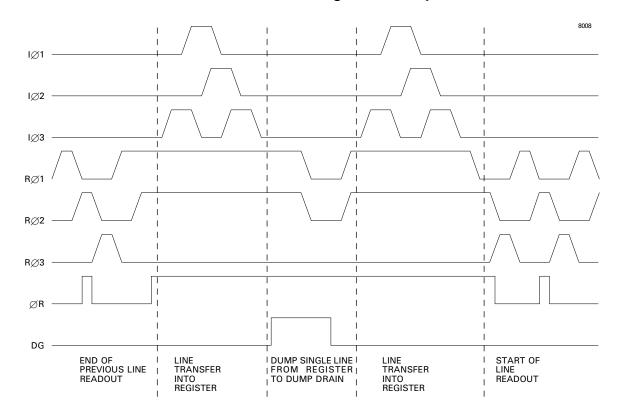
FRAME READOUT TIMING DIAGRAM



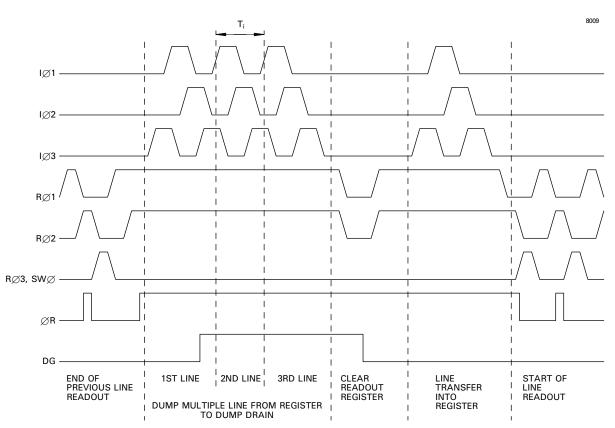
DETAIL OF LINE TRANSFER (Not to scale)



DETAIL OF VERTICAL LINE TRANSFER (Single line dump)

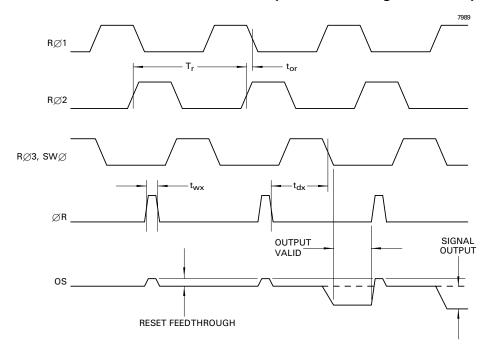


DETAIL OF VERTICAL LINE TRANSFER (Multiple line dump)

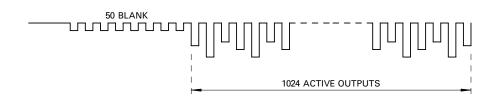


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DETAIL OF OUTPUT CLOCKING (Operation through both outputs)



LINE OUTPUT FORMAT (Split read-out operation)



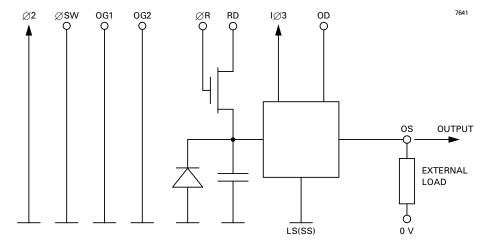
CLOCK TIMING REQUIREMENTS

Symbol	Description	Min	Typical	Max	
T _i	Image clock period	TBA	100 (see note 13)	see note 14	μs
t _{wi}	Image clock pulse width	TBA	50 (see note 13)	see note 14	μs
t _{ri}	Image clock pulse rise time (10 to 90%)	1	5	0.2T _i	μs
t _{fi}	Image clock pulse fall time (10 to 90%)	t _{ri}	t _{ri}	0.2T _i	μs
t _{oi}	Image clock pulse overlap	$(t_{ri} + t_{fi})/2$	2	0.2T _i	μs
t _{dir}	Delay time, IØ stop to RØ start	3	5	see note 14	μs
t _{dri}	Delay time, R∅ stop to I∅ start	1	2	see note 14	μs
T _r	Output register clock cycle period	300	see note 15	see note 14	ns
t _{rr}	Clock pulse rise time (10 to 90%)	50	0.1T _r	0.3T _r	ns
t _{fr}	Clock pulse fall time (10 to 90%)	t _{rr}	0.1T _r	0.3T _r	ns
t _{or}	Clock pulse overlap	20	0.5t _{rr}	0.1T _r	ns
t _{wx}	Reset pulse width	30	0.1T _r	0.3T _r	ns
t_{rx} , t_{fx}	Reset pulse rise and fall times	20	0.5t _{rr}	0.1T _r	ns
t _{dx}	Delay time, ØR low to RØ3 low	30	0.5T _r	0.8T _r	ns

NOTES

- 13. The transfer of a line of charge in back-thinned AIMO devices is affected by a pile-up of the holes used to suppress dark current, as they cannot easily flow to and from the substrate connection when the clocks change state. This problem is eased by extending the t_1 timing interval to 50 μ s and/or the use of higher drive pulse amplitudes.
- 14. No maximum other than that necessary to achieve an acceptable dark signal at the longer readout times.
- 15. As set by the readout period.

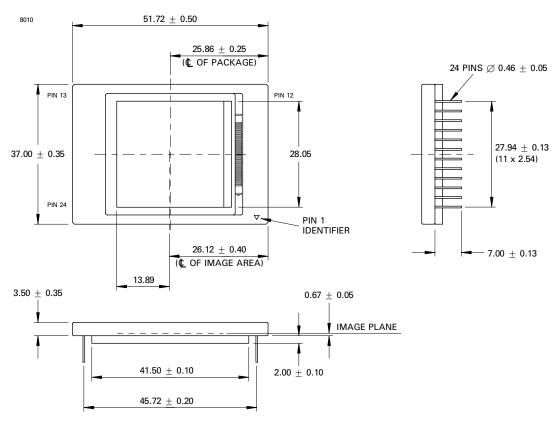
OUTPUT CIRCUIT



NOTES

- 16. The amplifier has a DC restoration circuit which is internally activated whenever IØ3 is high.
- 17. External load not critical; can be a 3 to 5 mA constant current supply or an appropriate load resistor.

OUTLINE (All dimensions in millimetres; dimensions without limits are nominal)



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ORDERING INFORMATION

Options include:

- Temporary quartz window
- Temporary glass window
- Fibre-optic coupling
- UV coating
- X-ray phosphor coating

For further information on the performance of these and other options, contact e2v technologies.

HANDLING CCD SENSORS

CCD sensors, in common with most high performance MOS IC devices, are static sensitive. In certain cases a discharge of static electricity may destroy or irreversibly degrade the device. Accordingly, full antistatic handling precautions should be taken whenever using a CCD sensor or module. These include:

- Working at a fully grounded workbench
- Operator wearing a grounded wrist strap
- All receiving socket pins to be positively grounded
- Unattended CCDs should not be left out of their conducting foam or socket.

Evidence of incorrect handling will invalidate the warranty. All devices are provided with internal protection circuits to the gate electrodes (pins 2, 7, 11, 14, 15, 16, 17, 18, 19, 20, 21, 22, 23) but not to the other pins.

HIGH ENERGY RADIATION

Device characteristics will change when subject to ionising radiation.

Users planning to operate CCDs in high radiation environments are advised to contact e2v technologies.

TEMPERATURE LIMITS

	Min	Typical	Max	
Storage	153	-	373	K
Operating	153	253	323	Κ
Operation or storage in humid of	conditio	ns may give	rise to i	ce on

Operation or storage in humid conditions may give rise to ice on the sensor surface on cooling, causing irreversible damage.

Maximum device heating/cooling . . . 5 K/min

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